

## PATENT ABSTRACTS OF JAPAN

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(21)Application number : 07-308519 (71)Applicant : CANON INC  
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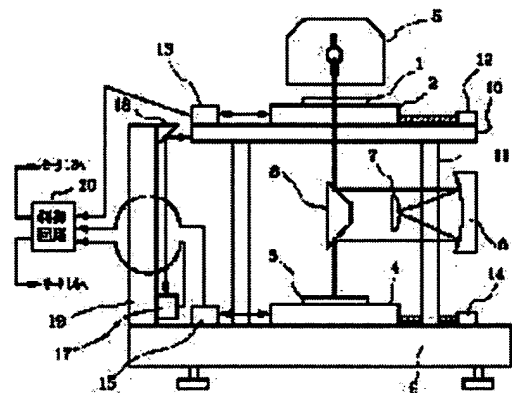
(54) SCANNING-TYPE EXPOSURE SYSTEM, DEVICE AND MANUFACTURE THEREOF

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a scanning exposure system which is capable of transferring a pattern accurately for exposure so as to cope with both the enhancement of a semiconductor device in degree of integration and the improvement of a liquid crystal display panel in fineness.

SOLUTION: A scanning exposure system is equipped with first moving means 2 and 12 which move an original plate 1, a first measuring means 13 which measures the position of the original plate 1, second moving means 4 and 14 which move a substrate 3, a second measuring means 15 which measures the position of the substrate 3, an illuminating optical system 9 which illuminates a pattern on the original plate 1, and a control means 20 which drives the first moving means 2 and 12 and the second moving means 4 and 14.

controlling them basing on measurements obtained from the first measuring means 13 and the second measuring means 15, wherein a scanning exposure operation is carried coat, moving the original plate 1 and the substrate 3 relative to the illuminating optical system 9 and keeping them aligned with each other, whereby a pattern on the original plate 1 is transferred onto the substrate 3. In this case, third measuring means 17 and 18 which measure a relative distance between the first measuring means 13 and the second measuring means 15 are provided, and the control means 20 drives the first moving means 2 and 12 or the second moving means 4 and 14 taking a relative position into consideration, whereby an alignment error caused by a change in relative position can be corrected.



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